

A Floating-Gate Trimmable High-Resolution DAC in Standard 0.25 μ m CMOS

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Abstract

We have built a 14-bit digital-to-analog converter (DAC) in a standard 0.25 μ m digital CMOS process. We use analog values stored on floating-gate p -channel MOSFETs to trim the DAC linearity. Because the storage is nonvolatile, we eliminate the need for continuous trimming. Our design has 6 untrimmable LSBs and 8 trimmable MSBs. The pre-trim differential nonlinearity (DNL) exceeded 130 LSBs; the post-trim DNL is less than 1.8 LSBs. We were able to trim the 8 MSBs to 0.5 LSB DNL; the 1.8 LSB error is due to an untrimmable bit. Because our DAC does not require continuous trimming, nor laser-trimmable resistors, it occupies only 0.17 mm² of die area and dissipates 11 mW at 100 MHz with a -10 dBm differential output.

Introduction

Emerging standards for communications systems require digital-to-analog converters (DACs) with sample rates in the hundreds of MS/s, and resolutions of 10–14 bits [1]. System-on-a-chip integration poses additional constraints including low power dissipation, small die area, and compatibility with standard digital CMOS processing. Current-steering DACs are attractive for these applications because they are fast and can drive an output load without a voltage buffer. Their static linearity, however, is limited by process mismatch.

To reduce mismatch-induced DAC errors, designers may use large devices, randomized layouts, laser trimming, continuous on-line electrical trimming, or other special techniques [2-4]. These techniques always increase die area and power dissipation substantially. What DAC designers need is a small, nonvolatile, electrically trimmable current source. Our floating-gate p FETs [5] perform this function.

Floating-Gate p FETs

A floating gate p FET is a conventional p -channel MOSFET with no direct electrical connection to its gate. Because we use the p FETs as current sources, we have no need for a gate input. Consequently, we do not use a second poly layer in the design, ensuring compatibility with standard digital CMOS processing. We use Fowler–Nordheim (FN) tunneling [6] to remove electrons from the floating gate, and impact-ionized hot-electron injection (IHEI) [7] to add electrons to the floating gate. Hot-electron injection in a p FET is a very precise and controllable process, so we can store accurate analog values on the floating gate [8]. We show a floating-gate p FET in Fig. 1.

The DAC

Fig. 2 shows a DAC block diagram. We use a segmented architecture with 6 binary-decoded lower LSBs (LLSB), 4 binary-decoded upper LSBs (ULSB) and 4 thermometer-decoded MSBs. The on-chip calibration circuitry trims the ULSB and MSB segments, while the LLSB segment relies on intrinsic matching and

is untrimmable. The digital circuitry comprises a static register to latch the 14-bit input word. The lower 10 flip-flops drive binary-weighted current-source arrays (6 LLSB and 4 ULSB), while upper 4 bits are thermometer decoded to drive 15 identical current sources.

Nineteen trim p FETs allow us to increase the outputs of the 4 ULSB and 15 thermometer-decoded MSB current sources. A p FET's current is unipolar, so the trim transistors by themselves do not provide bidirectional trimming. We add floating-gate p FET based current-regulation circuits to trim the current reference for each segment, allowing bidirectional trimming.

We trim the DAC using the following procedure: We first erase all the trim transistors by applying a high voltage (~ 7 V) to a global tunneling line. Then we trim each bit individually using electron injection, starting from the lowest ULSB. To trim ULSB bit i , we apply codeword $2^i - 1$, add an extra LSB, and call the output current a *target* current. Next we apply codeword 2^i , and trim bit i to cause the output current to match the target. To trim bit $i+1$ we apply codeword $2^{i+1} - 1$, add the extra LSB, and trim bit $i+1$ to match the new target. To trim the thermometer-decoded current sources we use the same procedure, but incrementing the codeword in units of 1024 rather than by powers-of-two. We continue until we have adjusted all 19 trim p FETs.

We induce electron injection by applying a negative voltage (-2.5 V) to a trim p FET's drain. We presently use off-chip supplies for the -2.5 V injection and $+7$ V tunneling voltages, but will incorporate on-chip charge pumps in future designs. For the data in this paper we trimmed using lab instruments, but DACs presently in fabrication have an on-chip comparator and state machine for autonomous trimming. Fig. 3 shows the measured DNL before and after trimming. The worst-case DNL of 1.8 LSBs is due to an untrimmable bit in the LSB segment. We trimmed all bits in the ULSB and MSB segments to a 0.5 DNL.

Our trim p FETs used 100 fF MOS capacitors for charge storage. We do not yet have data on long-term memory retention, but experiments running in the lab for 1 month show no evidence of charge loss to 14-bit accuracy at nominal temperature and supplies. Should charge loss become an issue for long (i.e. year) timescales, we can force the DAC to periodically self-trim during idle states or during power-up.

Fig. 4 shows a layout view of the DAC. The total active area is 0.17 mm²; the calibration circuitry occupies less than 10% of the area. The total power dissipation for a -10dBm output is 11 mW at 100 MHz with a 3.3 V power supply.

Conclusion

We have described a CMOS DAC that uses floating-gate p FETs for electrical trimming. Because we trim the current-source transistors themselves, the power and area are significantly less than existing high-linearity DACs. Furthermore, we can fabricate our DAC in any standard CMOS process in which we can build low-leakage floating-gate p FETs.

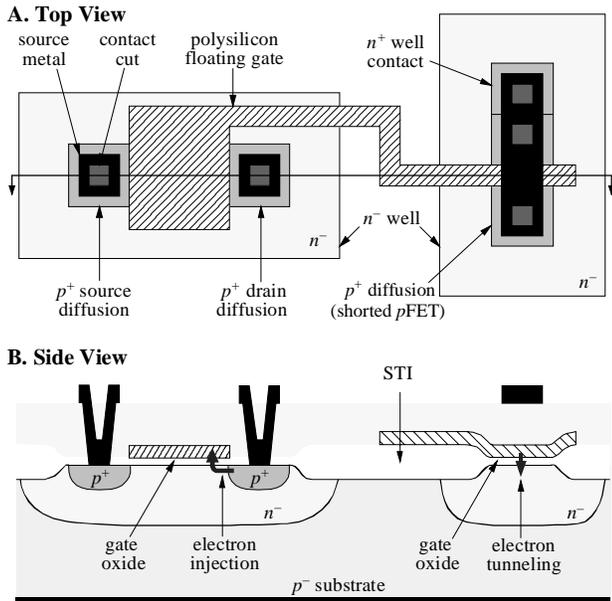


Figure 1. A floating-gate p FET and its associated tunneling junction, showing the electron tunneling and injection locations.

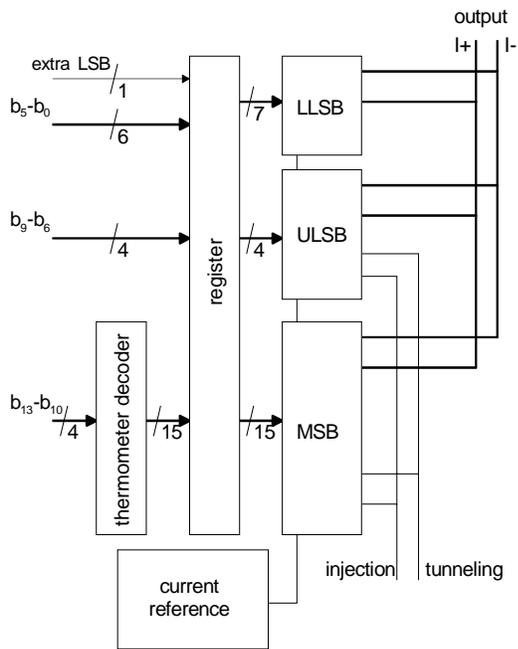


Figure 2. DAC block diagram. A digital register latches the input word, where the 4 MSBs are thermometer-decoded. LLSB is an untrimmable current source array, while ULSB and MSB are trimmable current-source arrays. The output is a differential current. The injection and tunneling lines control trimming.

References

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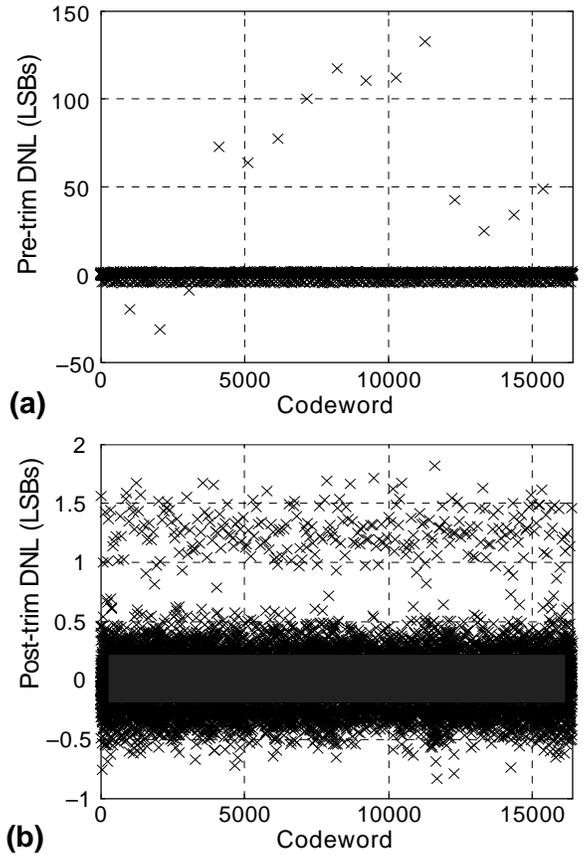


Figure 3. (a) DNL before trimming; (b) DNL after trimming. We trimmed the ULSBs and MSBs to a DNL of 0.5 LSBs; the points between 0.5 and 1.8 LSBs are due to an untrimmable bit

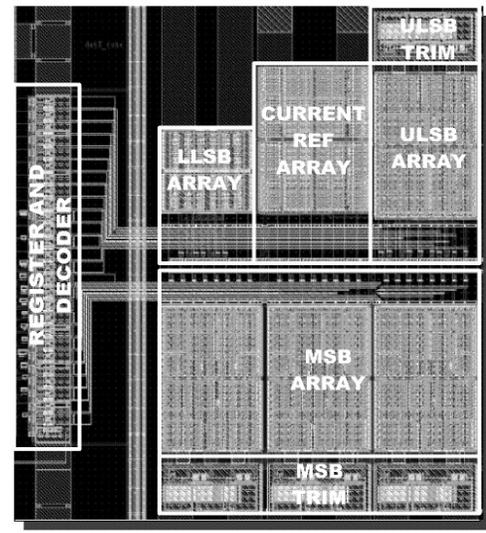


Figure 4. Layout view. The total active area is 0.17 mm^2 , the current-source arrays occupy 0.10 mm^2 , the trimming section occupies 0.02 mm^2 , and the digital circuits use 0.02 mm^2 .

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